

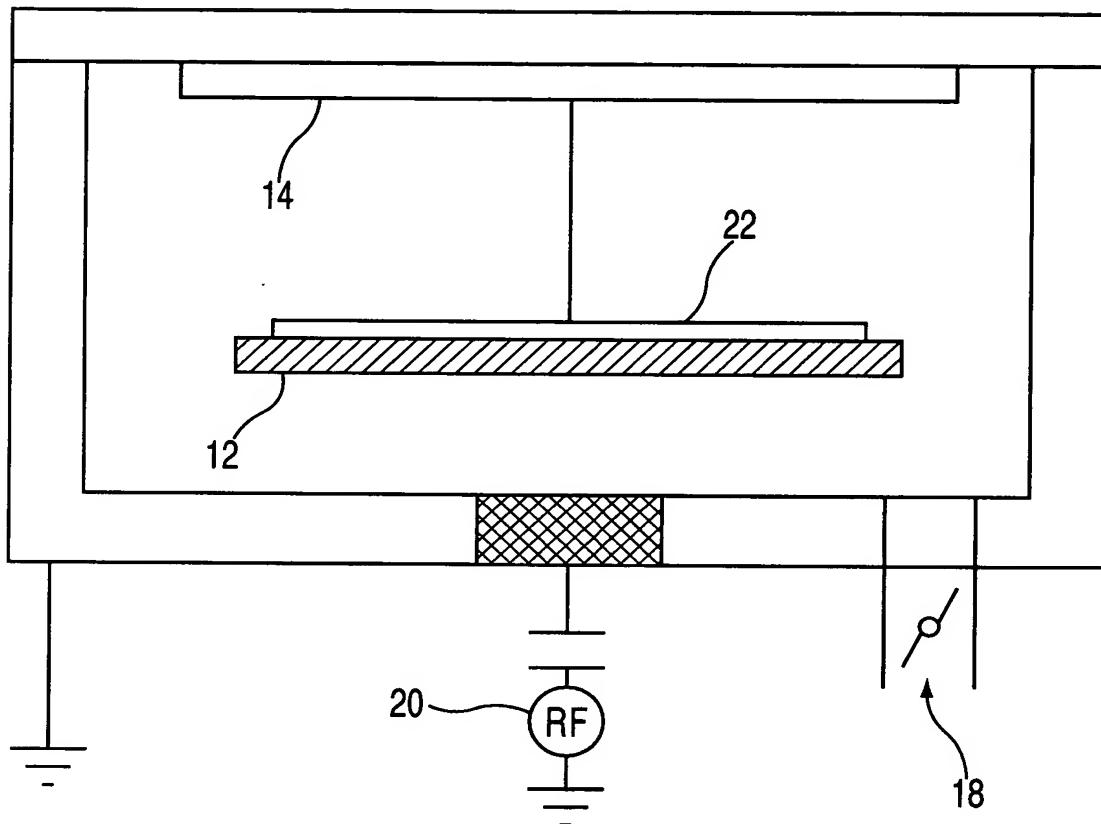
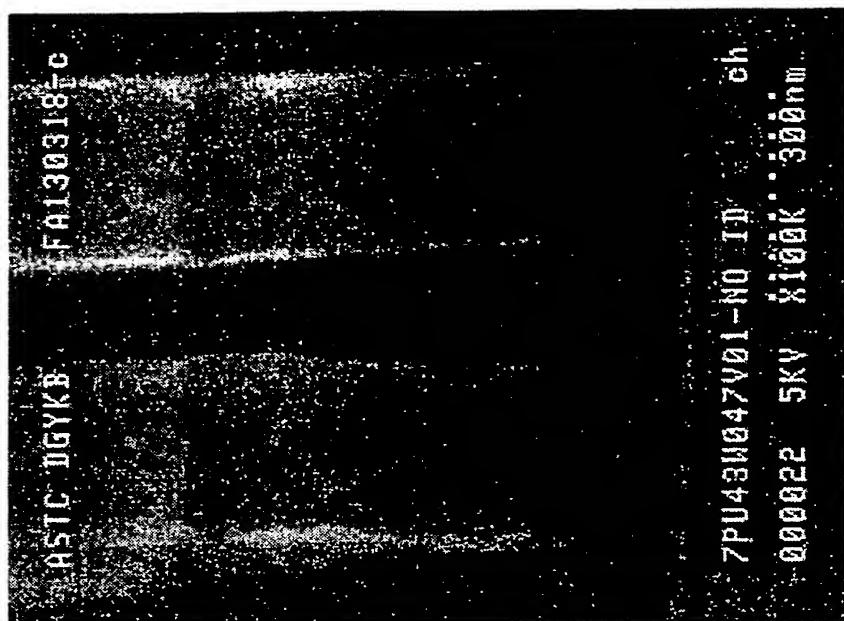
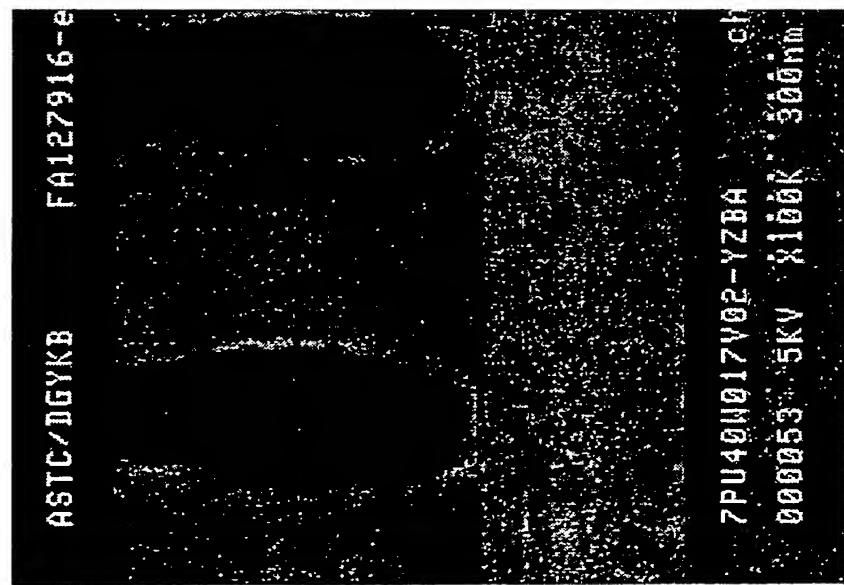
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FIG. 1



SICOH low k dielectric film formed from
3MS and non-nitrogen containing oxidant

FIG. 2B



SICOH low k dielectric film formed from
3MS and N₂O oxidant

FIG. 2A

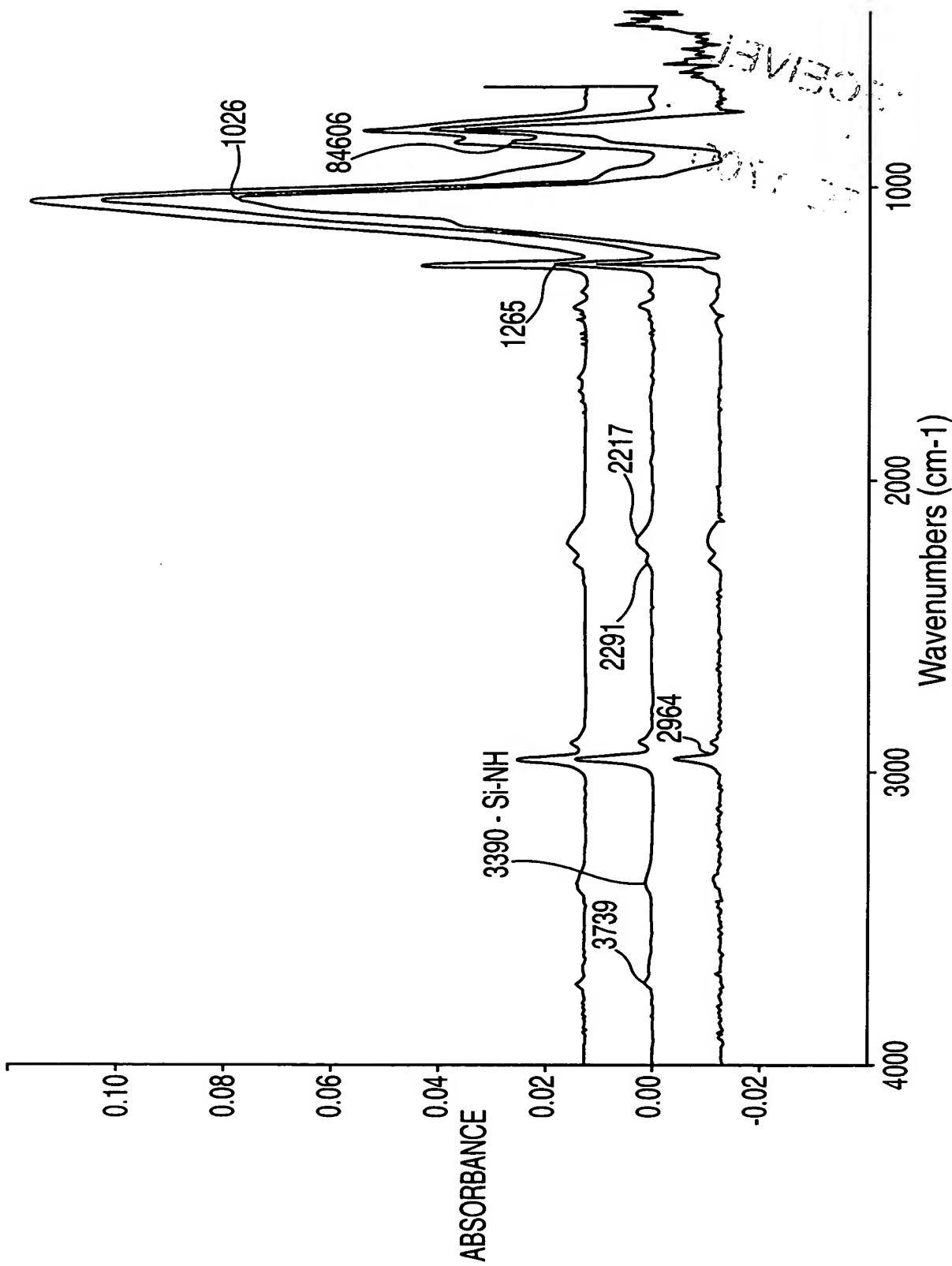


FIG. 3

FIG. 4

